
ERRATA

First-Principles-Derived Dynamics of a Surface Reaction: Fluorine Etching of Si(100)
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The F-Si-F three-body contribution to the potential in Eq. (5) has a misplaced bracket for the parameters presented in Table I. The equation should read

$$h_{\text{FSiF}} = [A_{\text{FSiF}}(\cos\theta - \cos 103^\circ)^2 - c_{\text{FSiF}}] \exp\{\gamma_{\text{FSiF}}[(r-a)^{-1} + (s-a)^{-1}]\}.$$